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7590 06/24/2009 COOK, ALEX, McFARRON, MANZO CUMMINGS & MEHLER, LTD. Suite 2850 200 West Adams Street Chicago, IL 60606				
EXAMINER FLETCHER III, WILLIAM P				
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**Please find below and/or attached an Office communication concerning this application or proceeding.**

The time period for reply, if any, is set in the attached communication.

## Office Action Summary

**Application No.**

09/747,731

**Applicant(s)**

YAMAZAKI ET AL.

**Examiner**

William P. Fletcher III

**Art Unit**

1792

**Period for Reply** -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

- 1) ☒ Responsive to communication(s) filed on 01 June 2009.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

- 4) ☒ Claim(s) 20-22, 37-40, 43-45, 48, 49 and 53-176 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 20-22, 37-40, 43-45, 48, 49 and 53-176 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some \* c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
  2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
  3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

- 1) ☐ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)
- 3) ☒ Information Disclosure Statement(s) (PTO/3508)  
Paper No(s)/Mail Date 5/20/09
- 4) ☐ Interview Summary (PTO-413)  
Paper No(s)/Mail Date \_\_\_\_\_
- 5) ☐ Notice of Informal Patent Application
- 6) ☐ Other: \_\_\_\_\_

***Continued Examination Under 37 CFR 1.114***

1. A request for continued examination under 37 CFR 1.114 was filed in this application after appeal to the Board of Patent Appeals and Interferences, but prior to a decision on the appeal. Since this application is eligible for continued examination under 37 CFR 1.114 and the fee set forth in 37 CFR 1.17(e) has been timely paid, the appeal has been withdrawn pursuant to 37 CFR 1.114 and prosecution in this application has been reopened pursuant to 37 CFR 1.114. Applicant's submissions filed on May 20, 2009 and June 1, 2009, has been entered.

***Response to Amendment***

2. Claims 20-22, 37-40, 43-45, 48, 49, and 53-176.

***Information Disclosure Statement***

3. The information disclosure statement filed May 20, 2009, has been considered.

***Response to Arguments***

4. Applicant has amended the claims as to matters of form and presents no new arguments traversing the rejections of record, which are maintained.

***Claim Rejections - 35 USC § 103***

10. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

11. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of

the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

12. *Claims 20–22, 44, 45, 48, 63, 70, 74, and 156, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A).*

With respect to claims 20 and 48, Arai teaches a method of manufacturing a display device in a cluster tool [abstract; c. 2, ll. 31 – 35; and c. 3, ll. 10 – 15]. Each processing chamber, of which there are at least two, has an evaporation source for the deposition of a material, which may be an organic electroluminescence material, on the substrate [c. 3, l. 66 – c. 5, l. 55]. As the substrate is transferred between chambers, layers of different EL materials are successively applied to produce the display device [c. 4, ll. 34 – 51 and c. 9, ll. 1 – 20]. Arai does not place any limitations on the layer deposition processes carried-out in the chambers.

Arai does not teach that: (i) fixing a mask to the substrate wherein the mask is located between the substrate and the first evaporation source; (ii) the first and second evaporation sources have a first direction longer than a second direction or that the

relative positions of the sources; or (iii) the substrates are repeatedly moved during deposition so that a same portion of the substrate is coated with the organic EL material at least twice.

With respect to (i), Nagayama teaches a process for forming an electroluminescent device by vapor deposition of the various layers that includes fixing a shadow mask between the substrate and a deposition source in order to form the desired patterned structures on the substrate [8:42-62]. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize a shadow mask in the claimed fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully forming the desired patterns of organic electroluminescent material on the substrate.

With respect to (ii), Grothe teaches that, when coating a substrate by vapor deposition, an evaporation source elongated in one dimension results in enhanced vapor density and deposition uniformity over the entire width of the substrate [c. 5, ll. 40 – 50 and 60 – 63]. It is the examiner's position that the source of Grothe reads on Appellant's source. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize, as the evaporation source, the evaporation source of Grothe. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of achieving enhanced vapor density and deposition uniformity, as taught by Grothe.

With respect to (iii), Monk teaches that, in a process where a substrate is coated from an evaporation source, it is known to move the substrate and the evaporation

source relative to each other [c. 1, ll. 9 – 21]. Doing so yields a uniform coating [c. 1, l. 15]. It would have been obvious to one of ordinary skill in the art to further modify the process of Arai so as to move the substrate and the evaporation sources relative to each other, as taught by Monk. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of yielding a uniform coating.

Lastly, it is well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

With respect to claim 21, none of the cited references teach cleaning the inside of the deposition chambers. It is the examiner's position, however, that cleaning the inside of a deposition chamber is a well-known means of eliminating contaminants in the chamber. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

With respect to claim 22, the transfer vacuum chamber 1 of Arai reads on a "conveyor chamber."

With respect to claims 44 and 45, it would have been obvious, to one of ordinary skill in the art, to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

With respect to claim 63, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 70, it is the examiner's position that the cluster tool arrangement, with its multiple coating chambers separated via a transfer chamber, reads on Appellant's claimed "chambers connected with each other through at least one gate."

With respect to claim 74, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 156, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

13. *Claims 37, 43, 48, 53, 64, 75, and 157, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), and Nagayama et al. (US 5,701,055 A).*

The teaching of Arai is detailed above. Arai does not place any limitations on the vapor deposition processes carried-out in the chambers.

Arai does not teach: (i) fixing a mask to the substrate wherein the mask is located between the substrate and the first evaporation source; (ii) that the first and second evaporation sources have a first direction longer than a second direction; or (iii) that the relative positions of the sources and the substrates are repeatedly moved during deposition so that a same portion of the substrate is coated with the organic EL material at least twice.

With respect to (i), Nagayama teaches a process for forming an electroluminescent device by vapor deposition of the various layers that includes fixing a shadow mask between the substrate and a deposition source in order to form the desired patterned structures on the substrate [8:42-62]. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize a shadow



mask in the claimed fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully forming the desired patterns of organic electroluminescent material on the substrate.

With respect to (ii), Grothe teaches that, when coating a substrate by vapor deposition, an evaporation source elongated in one dimension results in enhanced vapor density and deposition uniformity over the entire width of the substrate [c. 5, ll. 40 – 50 and 60 – 63]. It is the examiner's position that the source of Grothe reads on Appellant's source. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize, as the evaporation source, the evaporation source of Grothe. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of achieving enhanced vapor density and deposition uniformity, as taught by Grothe.

With respect to (iii), Bennett teaches that, in a vacuum vapor deposition process, moving the evaporation source with respect to the substrate improves deposition speed and uniformity [c. 3, ll. 1 – 10]. It would have been further obvious to one of ordinary skill in the art to modify the method of Arai so as to move the evaporation source relative to the substrate, as taught by Bennett. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of improving deposition speed and uniformity.

None of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness.

Consequently, it would have been obvious to one of ordinary skill in the art to do so. It would have been further obvious, to one of ordinary skill in the art, to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

With respect to claim 53, none of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

With respect to claim 64, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 75, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the

elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 157, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

14. *Claims 38, 48, 56, 65, 76, 153, and 158, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), Nagayama et al. (US 5,701,055 A), and Monk (US 4,187,801 A).*

The combined teaching of Arai, Bennett, Grothe, and Nagayama is detailed above. None of the references teach that the evaporation sources are longer than at least one edge of the substrate. Monk teaches that, in a vapor deposition method, it is conventional to treat a larger area than covered by the substrate to avoid edge effects [c. 1, ll. 17 – 20]. Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Bennett, and Grothe, so as to utilize an elongated

source that is longer than at least one edge of the substrate. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of avoiding edge effects, as suggested by Monk.

None of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so. It would have been further obvious, to one of ordinary skill in the art, to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

With respect to claim 53, none of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

With respect to claim 65, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and

arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 76, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 153, as noted above, the claimed relative movement would have been obvious based on the teaching of Bennett.

With respect to claim 158, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

15. *Claim 39, 48, 53, 57, 66, 77, and 159, are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US*

5,701,055 A), *Feuerstein et al.* (US 4,627,989 A), *Bennett* (US 2,435,997 A), and *Yamamoto et al.* (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent).

The teaching of Arai is detailed above. Arai does not place any limitations on the vapor deposition processes carried-out in the chambers.

Arai does not teach fixing a mask to the substrate wherein the mask is located between the substrate and the first evaporation source. Nagayama teaches a process for forming an electroluminescent device by vapor deposition of the various layers that includes fixing a shadow mask between the substrate and a deposition source in order to form the desired patterned structures on the substrate (8:42-62). It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize a shadow mask in the claimed fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully forming the desired patterns of organic electroluminescent material on the substrate.

Arai does not teach that first and second evaporation sources comprise a plurality of evaporation cells arranged along a first direction or that the relative positions of the sources are repeatedly moved with respect to the substrate during deposition so that a same portion of the substrate is coated at least twice. Feuerstein teaches a method of coating a substrate utilizing a vacuum evaporator comprising an elongated array of individually controllable vapor sources [c. 1, ll. 21 - 24; c. 2, ll. 40 - 45; c. 4, ll. 55 - 57; and c. 6, ll. 18 - 26]. Such a source facilitates greater control over deposition

thickness and uniformity [c. 2, ll. 41 - 45]. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize an evaporation source comprising a plurality of evaporation cells arranged along a first direction so as to achieve greater control over deposition thickness and uniformity, as suggested by Feuerstein.

It would have been further obvious to move the relative position of this source with respect to the substrate during evaporation. Bennett teaches that moving the source with respect to the substrate improves deposition speed and uniformity [see above]. Specifically moving the source instead of the substrate is considered advantageous because it requires a smaller vacuum chamber [c. 3, l. 72 - c. 4, l. 3].

None of the cited references teach coating the same portion of substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to do so.

It would have been obvious to one of ordinary skill in the art to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

Lastly, none of the cited references teach Appellant's limitation requiring "cleaning an inside of the evaporation chamber." Yamamoto teaches that, in the vapor deposition of organic thin films for EL devices, it is conventional to clean the parts

equipped in each chamber and the inside wall of the chambers after every deposition on the substrate (2:23-27). Doing so prevents contamination of the substrate by residual organic material having a tendency to peel-off of the chamber surfaces (2:63-3:8). Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to perform the conventional step of cleaning the deposition chamber. One of ordinary skill would have been motivated to do so by the desire and expectation of preventing contamination of the substrate.

The examiner notes that the body of Yamamoto's disclosure is directed to a method in which an additional set of cleaned parts is provided in each chamber, thereby eliminating the need to clean after each step, thereby saving time (5:45-8:30). Consequently, in the alternative, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to provide an additional set of cleaned parts to eliminate the need for repeated cleaning. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of reducing the processing time. The parts still need to be cleaned at some point, either before, during, or after the deposition process. Consequently, Yamamoto's invention also reads on Appellant's claimed "cleaning an inside of the evaporation chamber."

With respect to claim 53, none of the cited references teach coating the same portion of substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to do so.



With respect to claim 66, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 77, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 159, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

16. *Claim 40, 48, 58, 67, 78, 154, and 160, are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent) or, in the alternative, over Arai et al., in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al., Bennett, Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent).*

The combined teaching of Arai, Nagayama, Feuerstein, and Bennett is detailed above. Additionally, Feuerstein illustrates, but does not require, a source that is longer than at least one edge of the substrate [Fig. 1]. Nevertheless, it would have been obvious to utilize a source longer than at least one edge of the substrate to avoid edge effects, as taught by Monk [see above].

It would have been further obvious to move the relative position of this source with respect to the substrate during evaporation. Bennett teaches that moving the source with respect to the substrate improves deposition speed and uniformity [see above]. Specifically moving the source instead of the substrate is considered advantageous because it requires a smaller vacuum chamber [c. 3, l. 72 - c. 4, l. 3].

None of the cited references teach coating the same portion of substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to do so.

It would have been obvious to one of ordinary skill in the art to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

Lastly, none of the cited references teach Appellant's newly-added limitation requiring "cleaning an inside of the evaporation chamber." Yamamoto teaches that, in the vapor deposition of organic thin films for EL devices, it is conventional to clean the parts equipped in each chamber and the inside wall of the chambers after every deposition on the substrate (2:23-27). Doing so prevents contamination of the substrate by residual organic material having a tendency to peel-off of the chamber surfaces (2:63-3:8). Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to perform the conventional step of cleaning the deposition chamber. One of ordinary skill would have been motivated to do so by the desire and expectation of preventing contamination of the substrate.

The examiner notes that the body of Yamamoto's disclosure is directed to a method in which an additional set of cleaned parts is provided in each chamber, thereby eliminating the need to clean after each step, thereby saving time (5:45-8:30). Consequently, in the alternative, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to provide an additional set of cleaned parts to eliminate the need for repeated cleaning. One of

ordinary skill in the art would have been motivated to do so by the desire and expectation of reducing the processing time. The parts still need to be cleaned at some point, either before, during, or after the deposition process. Consequently, Yamamoto's invention also reads on Appellant's claimed "cleaning an inside of the evaporation chamber."

With respect to claim 67, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 78, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 154, as noted above, the claimed relative movement would have been obvious based on the teaching of Bennett.

With respect to claim 160, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

17. *Claim 49 is rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A) as applied to claim 20 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

18. *Claims 54, 68, 71, 79, and 161, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent).*

The teaching of Arai is detailed above. Arai does not place any limitations on the vapor deposition processes carried-out in the chambers.

Arai does not teach fixing a mask to the substrate wherein the mask is located between the substrate and the first evaporation source. Nagayama teaches a process for forming an electroluminescent device by vapor deposition of the various layers that includes fixing a shadow mask between the substrate and a deposition source in order to form the desired patterned structures on the substrate (8:42-62). It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize a shadow mask in the claimed fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully forming the desired patterns of organic electroluminescent material on the substrate.

Arai does not teach that the first and second evaporation sources have a first direction longer than a second direction or that the relative positions of the sources and the substrates are repeatedly moved during deposition so that a same portion of the substrate is coated with the organic EL material at least twice. Grothe teaches that, when coating a substrate by vapor deposition, an evaporation source elongated in one

dimension results in enhanced vapor density and deposition uniformity over the entire width of the substrate [c. 5, ll. 40 – 50 and 60 – 63]. It is the examiner's position that the source of Grothe reads on Appellant's source. It would have been obvious to one of ordinary skill in the art to modify the process of Arai so as to utilize, as the evaporation source, the evaporation source of Grothe. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of achieving enhanced vapor density and deposition uniformity, as taught by Grothe.

Bennett teaches that, in a vacuum vapor deposition process, moving the evaporation source with respect to the substrate improves deposition speed and uniformity [c. 3, ll. 1 – 10]. It would have been further obvious to one of ordinary skill in the art to modify the method of Arai so as to move the evaporation source relative to the substrate, as taught by Bennett. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of improving deposition speed and uniformity.

None of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

It would have been further obvious, to one of ordinary skill in the art, to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the

direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

Lastly, none of the cited references teach Appellant's newly-added limitation requiring "cleaning an inside of the evaporation chamber." Yamamoto teaches that, in the vapor deposition of organic thin films for EL devices, it is conventional to clean the parts equipped in each chamber and the inside wall of the chambers after every deposition on the substrate (2:23-27). Doing so prevents contamination of the substrate by residual organic material having a tendency to peel-off of the chamber surfaces (2:63-3:8). Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to perform the conventional step of cleaning the deposition chamber. One of ordinary skill would have been motivated to do so by the desire and expectation of preventing contamination of the substrate.

The examiner notes that the body of Yamamoto's disclosure is directed to a method in which an additional set of cleaned parts is provided in each chamber, thereby eliminating the need to clean after each step, thereby saving time (5:45-8:30). Consequently, in the alternative, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to provide an additional set of cleaned parts to eliminate the need for repeated cleaning. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of reducing the processing time. The parts still need to be cleaned at some point, either before, during, or after the deposition process. Consequently, Yamamoto's



invention also reads on Appellant's claimed "cleaning an inside of the evaporation chamber."

With respect to claim 68, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 79, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 161, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process

may advantageously manufacture any desired EL device, including a passive matrix display.

19. *Claims 55, 69, 72, 80, 155, and 162, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent).*

The combined teaching of Arai, Nagayama, Bennett, and Grothe is detailed above. None of the references teach that the evaporation sources are longer than at least one edge of the substrate. Monk teaches that, in a vapor deposition method, it is conventional to treat a larger area than covered by the substrate to avoid edge effects [c. 1, ll. 17 – 20]. Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Nagayama, Bennett, and Grothe, so as to utilize an elongated source that is longer than at least one edge of the substrate. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of avoiding edge effects, as suggested by Monk.

None of the cited references teach coating the same portion of the substrate twice. It is, nevertheless, well-known in the art of coating substrates to repeat a coating step the number of times required to build-up a coating of a desired thickness. Consequently, it would have been obvious to one of ordinary skill in the art to do so.

It would have been further obvious, to one of ordinary skill in the art, to optimize the orientation of the source with respect to the direction of motion so as to achieve the greatest efficiency and uniformity of coating. In particular, an orientation in which the direction of elongation of the source is perpendicular to the direction of motion allows coating the widest swath of substrate possible with each pass of the coating source.

Lastly, none of the cited references teach Appellant's limitation requiring "cleaning an inside of the evaporation chamber." Yamamoto teaches that, in the vapor deposition of organic thin films for EL devices, it is conventional to clean the parts equipped in each chamber and the inside wall of the chambers after every deposition on the substrate (2:23-27). Doing so prevents contamination of the substrate by residual organic material having a tendency to peel-off of the chamber surfaces (2:63-3:8). Consequently, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to perform the conventional step of cleaning the deposition chamber. One of ordinary skill would have been motivated to do so by the desire and expectation of preventing contamination of the substrate.

The examiner notes that the body of Yamamoto's disclosure is directed to a method in which an additional set of cleaned parts is provided in each chamber, thereby eliminating the need to clean after each step, thereby saving time (5:45-8:30). Consequently, in the alternative, it would have been obvious to one of ordinary skill in the art to modify the method of Arai, Feuerstein, and Bennett so as to provide an additional set of cleaned parts to eliminate the need for repeated cleaning. One of ordinary skill in the art would have been motivated to do so by the desire and

expectation of reducing the processing time. The parts still need to be cleaned at some point, either before, during, or after the deposition process. Consequently, Yamamoto's invention also reads on Appellant's claimed "cleaning an inside of the evaporation chamber."

With respect to claim 69, it is the examiner's position that the shape and distribution of the film thickness is a physical characteristic inherently arising from shape and arrangement of the evaporation source. Since this combination of references otherwise teaches all of Appellant's other method limitations — including the shape and arrangement of the evaporation source(s) — it is the examiner's position that the deposited film inherently possesses the characteristics recited in this claim.

With respect to claim 80, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 155, as noted above, the claimed relative movement would have been obvious based on the teaching of Bennett.

With respect to claim 162, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

20. *Claim 59 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A) and Grothe et al. (US 3,931,490 A), as applied to claim 37 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

21. *Claim 60 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), and Monk (US 4,187,801 A), as applied to claim 38 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

22. *Claim 61 rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 39 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

23. *Claim 62 is rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent) or, in the alternative, over Arai et al., in view of Nagayama et al., Feuerstein et al., Bennett, Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 40 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been

obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

24. *Claim 73 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A), as applied to claim 20 above, further in view of Mizutani et al. (US 6,326,726 B1).*

The combined teaching of Arai in view of Grothe, Monk, and Nagayama is detailed above.

None of the cited references teaches that the mask is fixed to the substrate by a magnet field.

Mizutani teaches a process of forming an electroluminescent device by vapor deposition of various organic layers through a shadow mask. The shadow mask is attached to the substrate utilizing an electromagnet (5:65-6:6). Doing so fits the mask securely against the substrate, facilitating the formation of a fine and accurate pattern (6:1-6).

It would have been obvious to one of ordinary skill in the art to modify the process of Arai in view of Grothe, Monk, and Nagayama so as to attach the mask to the



substrate utilizing an electromagnet. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of facilitating the formation of a fine and accurate pattern.

25. *Claims 81-88, 92-100, 141-144, 163, 164, and 166-176, are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A).*

The combined teaching of Arai in view of Grothe, Monk, and Nagayama is detailed above.

While Arai is silent with respect to precise nature of the organic EL layers deposited by the vapor process, Nagayama teaches forming a hole injecting layer and a light emitting layer over the hole injecting layer by a vapor deposition process (6:43-51 and 8:56-60). Nagayama further teaches that the structure includes a conducting film over the light emitting layer and a sealing layer over the light emitting layer.

Since Arai is non-limiting as to the precise nature of the organic EL layers deposited, it would have been obvious to one of ordinary skill in the art to modify the process so as to deposit the claimed structure since Nagayama teaches such a vapor-deposited structure is suitable for EL devices. Further, with respect to claim 85, it would have been obvious to one of ordinary skill in the art to seal the structure without exposure to the atmosphere (i.e., in the coating apparatus) so as to (i) prevent attack by

moisture, and (ii) simplify the process by not removing the unsealed structure from the apparatus for additional treatment.

With respect to claims 84, 88, 94, 97, and 100, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claims 141-144, the feature of these claims are taught by these references as noted above. See, in particular, the rejection of claim 96.

With respect to claims 163, 164, and 166-168, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

With respect to claims 169-176, the features of these claims are taught by or are obvious over the cited references as explained above. In particular, Nagayama teaches a rectangular mask opening.

26. *Claims 89-91 and 165 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A).*

The combined teaching of Arai in view of Grothe, Monk, and Nagayama is detailed above. Arai does not teach moving the mask by one pixel portion increments between deposition of materials. Again, Nakayama teaches a process for the vapor deposition of organic EL layers through a shadow mask in which the mask is moved by one pixel portion increments between deposition of various EL organic layers (Fig. 8). Since Arai is non-limiting as to the precise nature of the organic EL layer vapor deposition, it would have been obvious to one of ordinary skill in the art to modify the process so as to deposit in the claimed fashion since Nagayama teaches such a vapor-deposited structure is suitable for EL devices.

With respect to claim 91, none of the cited references explicitly states that the evaporation sources has a length exceeding 300 mm along the first direction. It is the examiner's position that, especially in view of the teaching of Grothe, it would have been obvious to one of ordinary skill in the art to select the elongated dimension of the source commensurate with the width of area to be covered. In other words, the length of the elongated dimension of the source is a result-effective variable effecting the degree of coverage and length of time of the overall coating process. The greater the area covered, the shorter the coating process. Consequently, it would have been obvious to

one of ordinary skill in the art to optimize the length of the elongated dimension of the coating source by routine experimentation, absent evidence of criticality. See MPEP 2144.05.

With respect to claim 165, Arai places no limitation on the sort of EL device manufactured. Consequently, it is the Examiner's position that the disclosed process may advantageously manufacture any desired EL device, including a passive matrix display.

27. *Claim 101 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A), as applied to claim 98 above, further in view of Spitzer et al. (US 5,258,325 A).*

The teachings of all of the cited references are described above. None of these teach that the display device is an active matrix electroluminescence display device.

Spitzer et al. teach that it is the electrode arrangement that distinguishes an active matrix device. Consequently, it is the examiner's position that it would have been obvious to utilize the above-cited methods of depositing organic electroluminescent material to manufacture an active matrix electroluminescent display device. One of ordinary skill in the art would have been motivated by the expectation of successfully manufacturing an active matrix EL display device since the deposition of the organic EL material does not determine whether or not the matrix is active.

28. *Claims 102-104 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A), as applied to claim 20 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

29. *Claims 105-107 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), and Nagayama et al. (US 5,701,055 A), as applied to claim 37 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and

conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

30. *Claims 108-110 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), Nagayama et al. (US 5,701,055 A), and Monk (US 4,187,801 A), as applied to claim 38 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

31. *Claims 111-113 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 39 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

32. *Claims 114-116 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent) or, in the alternative, over Arai et al., in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al., Bennett, Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US*

*6,179,923 B1 provided as English-language equivalent), as applied to claim 340 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

33. *Claims 117-119 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 54 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70).



Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

34. *Claims 120-122 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Bennett (US 2,435,997 A), Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 55 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

35. *Claims 123-128 and 132-138 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490*

*A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A), as applied to claims 81, 85, 92, 95, and 98, respectively, above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70). Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

36. *Claims 129-131 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai et al. (US 5,817,366 A) in view of Grothe et al. (US 3,931,490 A), Monk (US 4,187,801 A), and Nagayama et al. (US 5,701,055 A), as applied to claim 129-131 above, further in view of Bertelsen (US 3,110,620 A).*

None of the cited references explicitly teach the features of these claims. Bertelsen teaches a process in which multiple layers (including transparent and conductive layers) are vapor deposited on a substrate, optionally via a mask, in which the substrate is situated above an evaporation coating source (Fig. 3 and 3:55-70).

Consequently, it would have been obvious to one of ordinary skill in the art to modify the process of these references so as to arrange the substrate, mask, and coating source in this fashion. One of ordinary skill in the art would have been motivated to do so by the desire and expectation of successfully coating the substrate.

37. *Claims 145-148 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 39 above, further in view of either Noguchi et al. (US 4,596,735 A) or Martin (US 4,469,719 A).*

Arai, Nagayama, Feuerstein, Bennett, and Yamamoto are cited herein again as detailed above.

None of these references teaches the claimed source-mask distance.

Both Noguchi and Martin teach that the source-mask distance is a result-effective variable effecting various properties of the deposited film.

Consequently, it would have been obvious to one of ordinary skill in the art, absent evidence of criticality, to optimize this distance by routine experimentation. See MPEP 2144.05.

38. *Claims 149-152 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Arai et al. (US 5,817,366 A), in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al. (US 4,627,989 A), Bennett (US 2,435,997 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent) or, in the alternative, over Arai et al., in view of Nagayama et al. (US 5,701,055 A), Feuerstein et al., Bennett, Monk (US 4,187,801 A), and Yamamoto et al. (JP 11-61386 A, US 6,179,923 B1 provided as English-language equivalent), as applied to claim 40 above, further in view of either Noguchi et al. (US 4,596,735 A) or Martin (US 4,469,719 A).*

Arai, Nagayama, Feuerstein, Bennett, Monk, and Yamamoto are cited herein again as detailed above.

None of these references teaches the claimed source-mask distance.

Both Noguchi and Martin teach that the source-mask distance is a result-effective variable effecting various properties of the deposited film.

Consequently, it would have been obvious to one of ordinary skill in the art, absent evidence of criticality, to optimize this distance by routine experimentation. See MPEP 2144.05.

### **Conclusion**

39. All claims are drawn to the same invention claimed in the application prior to the entry of the submission under 37 CFR 1.114 and could have been finally rejected on the

grounds and art of record in the next Office action if they had been entered in the application prior to entry under 37 CFR 1.114. Accordingly, **THIS ACTION IS MADE FINAL** even though it is a first action after the filing of a request for continued examination and the submission under 37 CFR 1.114. See MPEP § 706.07(b). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to William P. Fletcher III whose telephone number is (571) 272-1419. The examiner can normally be reached on Sunday, 5:00 AM - 12:00 PM and Monday through Friday, 5:00 AM - 3:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy H. Meeks can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/William Phillip Fletcher III/  
Primary Examiner, Art Unit 1792

June 21, 2009